

SEMICONDUCTOR CONDUCTIVE PATTERN  
FORMATION METHOD

ABSTRACT OF THE INVENTION

5 A method for forming a conductive or magnetic  
pattern for a semiconductor or other electronic device  
includes patterning a mask layer outwardly from a  
conductive layer of the semiconductor device. The  
patterning defines portions of the conductive layer where  
vias through the conductive layer are desired. The  
method also includes exposing the semiconductor device to  
a plasma. The plasma converts the unmasked portions of  
10 the conductive layer into a compound. The method further  
includes exposing the semiconductor device to a treatment  
process to selectively remove the compound. The mask  
layer may be removed either before or after removal of  
the compound, thereby providing the unmasked conductive  
15 layer in the desired pattern.

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